

ABSTRACT

The present disclosure provides an ignition chamber of a semiconductor process equipment, a semiconductor process equipment, and a control method. In the ignition chamber of the semiconductor process equipment, one end of a communication pipeline and one end of a purge pipeline respectively communicate with a first end of a combustion chamber, and the other end of the purge pipeline is configured to communicate with a combustion-supporting gas source; and one end of an exhaust pipeline, one end of a first gas inlet pipeline, and one end of a second gas inlet pipeline respectively communicate with a second end of the combustion chamber opposite to the first end of the combustion chamber, the other end of one of the first gas inlet pipeline and the second gas inlet pipeline is configured to communicate with a combustible gas source, and the other end of the other of the first gas inlet pipeline and the second gas inlet pipeline is configured to communicate with the combustion-supporting gas source.

The ignition chamber can solve the problem that when purging is performed on an existing ignition chamber before the existing ignition chamber is used for a wet oxidation process, part of oxygen flows into a process chamber and undergoes a dry oxidation process with a workpiece to be processed, which hinders the subsequent wet oxidation process.